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NEW PHOTOSENSITIVE RESINS @405 nm: APPLICATIONS TO 3D PRINTING

AUDE-HÉLOÏSE BONARDI¹, SORAYA ZAHOUILY¹, CÉLINE DIETLIN¹, FABRICE MORLET-SAVARY¹, FRÉDÉRIC DUMUR², DIDIER GIGMES², SÉGOLÈNE VILLOTTE², JACQUES LALEVÉE¹

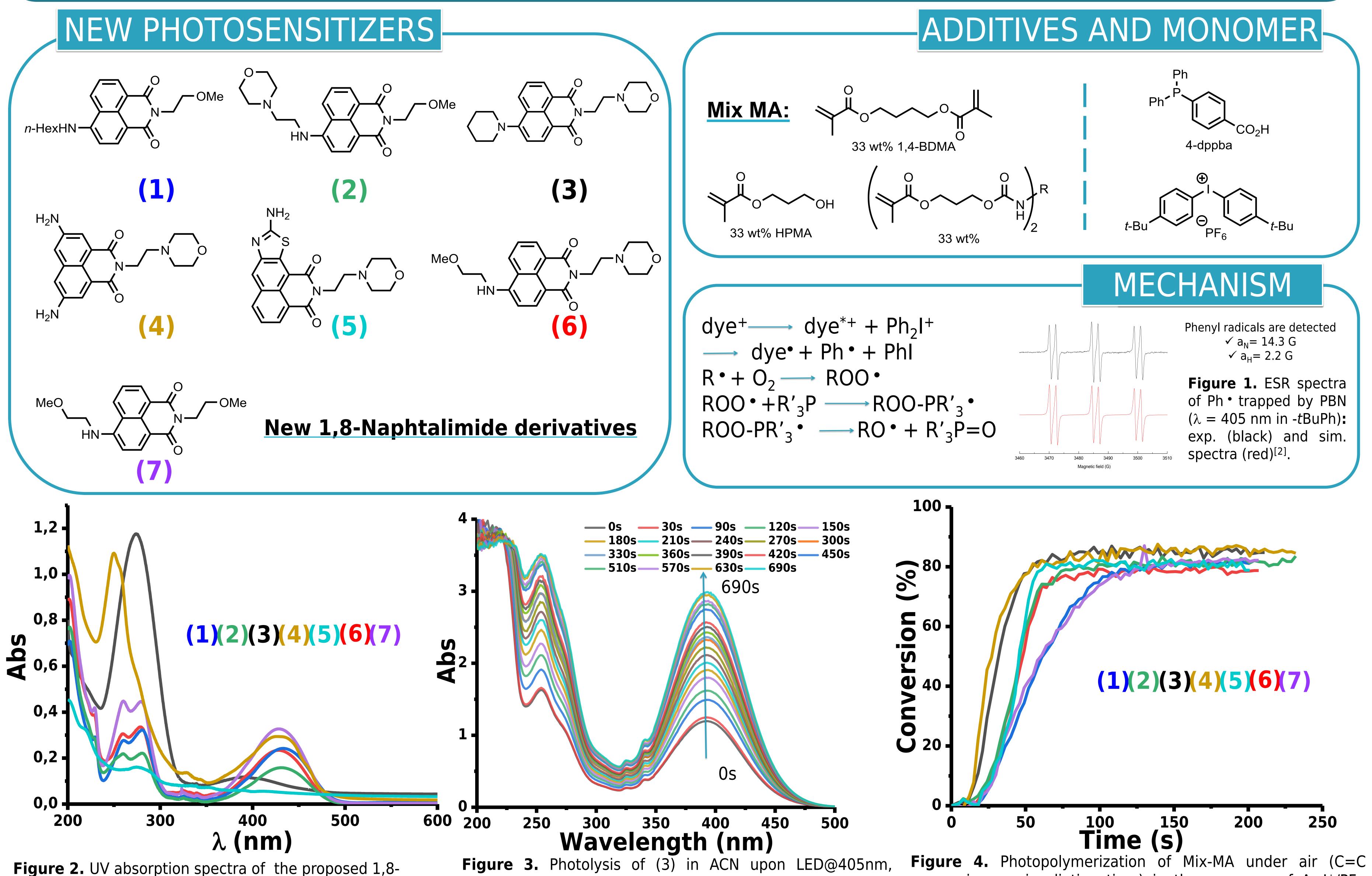
¹Institut de Science des Matériaux de Mulhouse IS2M – UMR CNRS 7361 – UHA, 15, rue Jean Starcky, 68057 Mulhouse Cedex, France,

<u>Jacques.lalevee@uha.fr</u>

ABSTRACT

²Aix-Marseille Univ., CNRS, ICR, F-13397 Marseille, France

The field of 3D printing is today a hot topic. The development of new resins more efficient for such applications is today a real challenge. To this purpose, photosensitive systems are the key point to develop new high performance 3D printing system. The photopolymerization allows the transformation of mutifunctional monomer or prepolymer into highly crosslinked networks by action of light^[1]. According to the literature, photopolymerization of (meth)acrylate or epoxy monomers usually requires UV-curing. As UV wavelengths are known to be noxious, the development of new free radical initiating systems upon longer (safer) wavelengths irradiation such as 405 nm is crucial.



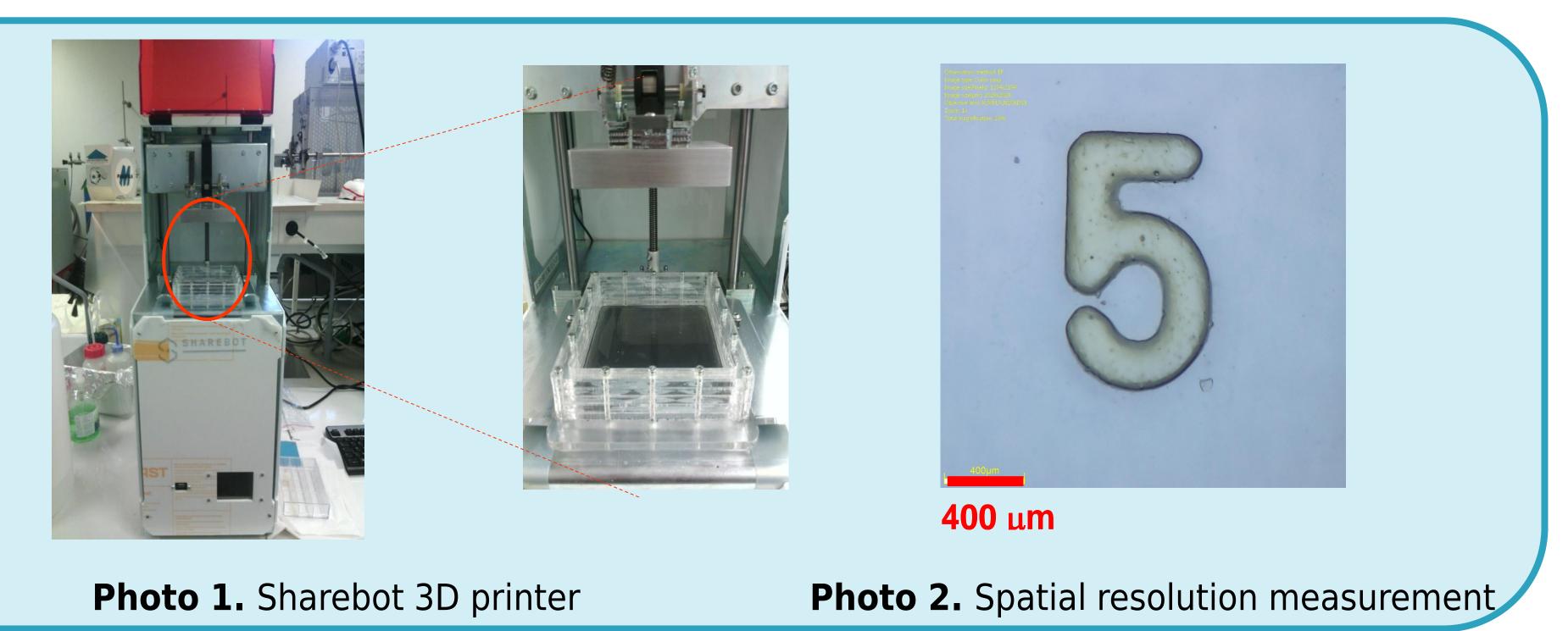
naphtalimide derivates in ACN

110mW/cm²: UVvis spectra for different irradiation times

conversion vs. irradiation time) in the presence of Ar_2I^+/PF_6^- (3wt%), 4-dppba (2wt%) and 1,8-naphtalimide derivates (0.1wt%), LED@405nm, thickness=1,4mm

CONCLUSION AND PERSPECTIVES

- -Interesting light absorption properties in the near-UV range
- -Very good conversions obtained
- -Fast photopolymerization upon safe irradiation conditions (faster for polymerization of larger objects)
 -Compatibility with Sharebot 3D printer@405 nm (Photo 1)
- -Measure of spatial resolution (in progress) (Photo 2) -Acknowledgments: Sharebot for the 3D printer



REFERENCES

^[1] J.-P. Fouassier, J. Lalevée, *Photoinitiators for polymer synthesis: scope, reactivity and efficiency.* Weinheim: Wiley-VCH.; **2012.** ^[2] M. Bouzrati-Zerelli; M. Maier; C. P. Fik; C. Dietlin; F. Morlet-Savary; J.-P. Fouassier; J. Klee; J. Lalevée; A, *Polym. Int.* **2016**, 10.1002/pi.5262.